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INFORMATION DISCLOSURE STATEMENT BY APPLICANT						Applicants				
	(Us	e several sh	eets if nec	essary)	Yong-Bae Kim et al.					
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*Examiner Initial		Document Number	Date	Name	Class	Subclas	s If	Filing Date If Appropriate		
K-cc	AA	5,874,367	2/23/99	Dobson	438	787		-		
	AB	6,028,015	2/22/00	Wang et al.	438	789	3/29/9	99		
	AC	6,114,259	9/5/00	Sukharev et al.	438	789	7/27/9	99		
	AD	6,147,012	11/14/00	Sukharev et al.	438	787	11/12	/99		
	AE	6,204,192	3/20/01	Zhao et al.	438	723	3/29/9	99 .		
	AF	6,232,658	5/15/01	Catabay et al.	257	701	6/30/9	9		
	AG	5,314,845	5/24/94	Lee et al.	437	238	2/2/90)		
K-ic	AH	5,915,203	6/22/99	Sengupta et al.	438	669	6/10/9	7		
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OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

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Bothra, S., et al., "Integration of 0.25 μm Three and Five Level
Interconnect System for High Performance ASIC", 1997 Proceedings Fourteenth
International VMIC Conference, Santa Clara, CA, June 10-12, 1997, pp.43-48.

AS

Dobson, C.D., et al., "Advanced SiO₂ Planarization Using Silane and H₂O₂",
Semiconductor International, December 1994, pp. 85-88.

McClatchie, S., et al., "Low Dielectric Constant Oxide Films Deposited Using
CVD Techniques", 1998 Proceedings Fourth International DUMIC Conference,
February 16-17, 1998, pp. 311-318.

Examiner . C. Valle

Date Considered

3-1-01

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant.

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K-06	BA	6,235,453	5/2001	You et al.	430	316			
į	вв	6,417,080	7/2002	Yokoshima	438	514			
	BC	6,316,354	11/2001	Hu	438	624			
	BD	6,281,589	8/2001	Nguyen et al.	257	758			
	BE	6,030,901	2/2000	Hopper et al.	204.	192.36			
·	BF	5,939,241	8/1999	Leu et al.	430	318			
K-(c	BG	6,281,135	8/2001	Han et al.	438	725			
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OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)									
k-ic	BR Peters, Laura, "Low-k Dielectrics: Will Spin-On or CVD Prevail?", Semiconductor International, Vol. 23, No. 6, June, 2000, pp. 108-110, 114, 116, 118, 122, and 124.							114,	

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

BR Peters, Laura, "Low-k Dielectrics: Will Spin-On or CVD Prevail?",
Semiconductor International, Vol. 23, No. 6, June, 2000, pp. 108-110, 114,
116, 118, 122, and 124.

BS Peters, Laura, "Pursuing the Perfect Low-k Dielectric", Semiconductor
International, Vol. 21, No. 10, September, 1998, pp. 64-66, 68, 70, 72,
and 74.

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Examiner (...

Date Considered

3-1-01

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U.S. Department of Commerce. Patent and Trademark Office						Docket No. Serial			
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INFORMATION DISCLOSURE STATEMENT BY APPLICANT						Applicants			
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*Examiner Initial		Document Number	Date	Name	Class	Subclas	s If	Filing Date If Appropriate	
K-ic	CA	5,904,154	5/18/99	Chien et al.	134	1.2	7/24/97		
	СВ	5,882,489	3/16/99	Bersin et al.	204	192.35	4/26/96		
	CC	5,858,879	1/12/99	Chao et al.	438	725	6/6/97		
	CD	3,012,861	12/12/61	Ling	23	223.5	1/15/60		
	CE	3,178,392	4/13/65	Kriner	260	46.5	4/9/62		
	CF	3,832,202	8/27/74	Ritchie	106	287	8/8/72		
	CG	3,920,865	11/18/75	Läufer et al.	427	220	4/6/72		
	СН	4,705,725	11/10/87	Glajch et al.	428	405	11/28/86		
	CI	5,194,333	3/16/93	Ohnaka et al.	428	405	12/18/90		
	CJ	5,874,745	2/23/99	Kuo	257	59	8/5/97		
K-li c	CK	6,440,295	8/02	Wang	205	640			
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K-er	CT	DE 198 04 375 Al	7/1/99	Germany	H 01 L	21/312		x	
	CM	EP 0 706 216 A2	4/10/96	Europe	H 01 L	23/532	N/A		
	CN	EP 0 949 663 A2	10/13/99	Europe	H 01 L	21/312	N/A		
	со	63003437	1/8/88	Japan	H 01 L	21/90	X-Abstract Only		
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FORM PTO-1449 (Modified)

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant.

FORM PTO-1449 (Modified) U.S. Department of Commerce, Patent and Trademark Office					Docket No. Serial		Serial No.		
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INFORMATION DISCLOSURE STATEMENT BY APPLICANT					Applicants				
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*Examiner Initial			Document Number	Date	Name	Class	Subclass	Filing Da If Appropria	
K-iL		DA	6,066,574	5,23/00	You et al.	438	781	11/6/98	
		DB	6,051,477	4/18/00	Nam	438	404	10/22/96	
		DC	6,025,263	2/15/00	Tsai et al.	438	624	9/11/97	
		DD	5,939,763	8/17/99	Hao et al.	257	411	9/5/96	
		DE	5,864,172	1/26/99	Kapoor et al.	257	634	8/13/96	
		DF	5,688,724	11/18/97	Yoon et al.	437	235	12/23/94	
		DG	5,470,801	11/28/95	Kapoor et al.	437	238	6/28/93	
	_	DH	5,364,800	11/15/94	Joyner	437	28	6/24/93	
		DI	4,771,328	9/13/88	Malaviya et al.	357	49	11/24/86	
. 4	-cc	DJ	3,652,331	3/28/72	Yamaząki	117	201	3/13/69	
		DK					 		
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k	DR Koda, Seiichiro, et al., "A Study of Inhibition Effects for Silane Combustion by Additive Gases", Combustion and Flame, Vol. 73, No. 2, August, 1988, pp. 187-194.								
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